Amendment to the Claims:

This listing of claims replaces all prior versions, and listings, of claims in the application:

1. (Currently Amended) A method comprising:

applying carbon dioxide to a surface of a reticle;

forming a solid carbon dioxide layer on the surface of the reticle at a temperature below a sublimation temperature of carbon dioxide, the solid carbon dioxide layer preventing particles from contacting the surface of the reticle;

placing the reticle inside a lithography tool;

removing the solid carbon dioxide layer from the surface of the reticle inside the lithography tool; and

spraying the surface of the reticle with carbon dioxide inside the a lithography tool.

- 2. (Original) The method of Claim 1, wherein said applying comprises spraying the surface of the reticle with carbon dioxide and removing particles from the surface with carbon dioxide snow.
- 3. (Original) The method of Claim 1, wherein said applying comprises spraying carbon dioxide snow at a grazing angle with respect to the surface of the reticle.

- 4. (Original) The method of Claim 1, further comprising cooling the reticle to a temperature below a sublimation temperature of carbon dioxide before said forming a solid carbon dioxide layer on the surface of the reticle.
- 5. (Original) The method of Claim 1, wherein said forming a solid carbon dioxide layer on the surface of the reticle comprises spraying carbon dioxide snow at a substantially 90 degree angle with respect to the surface of the reticle.
- 6. (Original) The method of Claim 1, further comprising: enclosing the reticle with the solid carbon dioxide layer in a carrier; and

maintaining a temperature around the reticle below a sublimation temperature of carbon dioxide.

- 7. (Canceled).
- 8. (Original) The method of Claim 1, further comprising raising a temperature around the reticle above a carbon dioxide sublimation temperature.
 - 9-10. (Canceled).

- 11. (Original) The method of Claim 1, further comprising reflecting radiation off the surface of the reticle in a lithography tool.
- 12. (Original) The method of Claim 1, further comprising reflecting extreme ultraviolet radiation off the surface of the reticle in a lithography tool.
 - 13-20. (Canceled)
 - 21-29. (Not Entered)
 - 30. (New) A method comprising:

spraying carbon dioxide to remove particles on a surface of a reticle:

cooling the reticle to a temperature below a sublimation temperature of carbon dioxide;

forming a solid carbon dioxide layer on the surface of the cooled reticle to prevent particles from contacting the surface of the reticle;

placing the reticle inside a lithography tool;

warming the reticle inside the lithography tool to sublimate the solid carbon dioxide layer; and

spraying the surface of the reticle with carbon dioxide inside the lithography tool to remove particles on the surface.

31. (New) A method comprising:

forming a solid carbon dioxide layer on a surface of a pellicle at a temperature below a sublimation temperature of carbon dioxide to prevent particles from contacting the surface of the pellicle;

placing a pellicle over the reticle;

placing the reticle inside a lithography tool; and

removing the solid carbon dioxide layer inside the

lithography tool without removing the pellicle.